

IN THE SPECIFICATION

Please replace the paragraph beginning at page 51, line 18, with the following rewritten paragraph:

The patterning plated substrate (A) provided with a pattern of 40 μm pitch in a mask dimension (removed pattern of 30 μm width/remaining pattern of 10 μm width) was observed by a light microscope and a scanning electron microscope, and the substrate was evaluated based on the following criteria.

Please replace the paragraph beginning at page 52, line 10, with the following rewritten paragraph:

The patterning plated substrate (A) provided with a pattern of 40 μm pitch in a mask dimension (removed pattern of 30 μm width/remaining pattern of 10 μm width) was observed by a light microscope and a scanning electron microscope, and the substrate was evaluated based on the following criteria.